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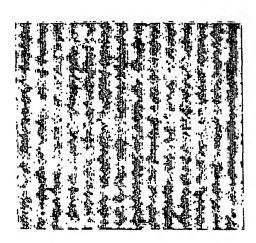
- (71) Applicant (for all designated States except US): INFM IS-TITUTO NAZIONALE PER LA FISICA DELLA MA-TERIA [IT/IT]; Corso F. Perrone 24, I-16152 GENOVA (IT).
- (72) Inventors; and
- (75) Inventors/Applicants (for US only): CAPUTO, Roberto [IT/IT]; Via Parigi 21, I-87036 RENDE (Cosenza) (IT). UMETON, Cesare [IT/IT]; Via Tevere 68, I-87036 RENDE (Cosenza) (IT). VELTRI, Alessandro [IT/IT]; Via P. Borsellino Fabbricato S.E.M., s.n., I-87100 COSENZA (IT). SUKHOV, Andrey [RU/RU]; pr.

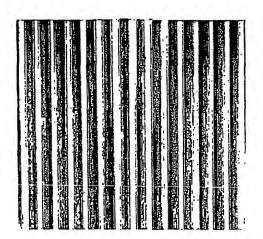
Karamzina 9 - Apt. 60, MOSCOW, 117463 (RU). TABIRYAN, Nelson [AM/US]; 809 South Orlando Avenue - Suite I, WINTER PARK, Florida 32789 (US).

- (74) Agent: RAMBELLI, Paolo; Corso Regio Parco 27, I-10152 TORINO (IT).
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(54) Title: HOLOGRAPHIC DIFFRACTION GRATING, PROCESS FOR ITS PREPARATION AND ELECTRO-OPTICAL DEVICES INCLUDING THE SAME





(57) Abstract: Composite polymer/liquid crystal material having a holographic grating structure formed by an alternating ordered succession of polymer layers and nematic liquid crystal layers. The nematic liquid crystal layers comprise an ordered nematic monophase region which is substantially free from liquid crystal droplets. Furthermore, the holographic grating structure is obtained by a process which comprises the steps of: -heating a mixture of a photoinitiator, a monomer and a nematic liquid crystal above the nematic/isotropic phase transition temperature, in order to prevent phase separation and isotropic/nematic phase transition of the liquid crystal; - illumination of the mixture with an interference pattern to induce polymerisation; - slow cooling of the mixture at a rate lower than 0,3°C/mixture, to achieve a complete orientation of the liquid crystal director, and below the isotropic/nematic transition temperature.



WO 2005/006065 A3



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